

31/9
4-11-00
mharrian
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Hisashi OHTANI et al.

Serial No.: 08/807,737

Filed: February 27, 1997

For: METHOD FOR
MANUFACTURING
SEMICONDUCTOR DEVICE



Group Art Unit: 2813

Examiner: M. Sulsky

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents and Trademarks, Washington, D.C. 20231, on 3-31-00.

Deborah Taylor

AMENDMENT

Assistant Commissioner for Patents
Washington, D. C. 20231

Sir:

In response to the Office Action mailed October 4, 1999, please amend the above-identified application as follows.

IN THE CLAIMS:

Please add the following new claims 78-83:

--78. A method according to claim 19 wherein said silicon nitride film is in contact with said semiconductor film.

79. A method according to claim 24 wherein said silicon nitride film is in contact with said semiconductor film.

80. A method according to claim 36 wherein said silicon nitride film is in contact with said semiconductor film.

4 81. A method according to claim 60 wherein said silicon nitride film is in contact with said semiconductor film.

04/06/2000 CVORACHA 00000032 08807737

01 FC:103

108.00 OP

39

RECEIVED

APR 07 2000

TECHNOLOGY CENTER 2800

6